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## Deposition rate dependent phase/mechanical property evolution in Zirconia and Ceria-Zirconia thin film by EB-PVD Technique

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### Abstract:

Pure zirconia ( $ZrO_2$ ) and ceria (16 mol%) stabilized zirconia (CeSZr) thin films were prepared by electron beam physical vapor deposition with varying deposition rates (1, 4 and 8 Å/s) in order to correlate the phase changes to the mechanical property. X-ray diffraction and Raman spectra results indicate the presence of mixed monoclinic and tetragonal phases in  $ZrO_2$  film, but tetragonal phase dominated at lower deposition rate. However, irrespective of the deposition rate, cerium addition to  $ZrO_2$  resulted in complete stabilization of tetragonal phase. Depending on the presence of dual ( $ZrO_2$ ) or single (CeSZr) phase either surface cracks or well-connected grain structure, respectively, was observed. However, CeSZr film showed a four-fold increase in hardness in comparison to  $ZrO_2$  which can be attributed to the complete stabilization of tetragonal phase that hinders the crack propagation along the grain. Plastic deformation of CeSZr film was found to be  $1.80 \times 10^{-2}$  GPa, which is about ~55% higher as compared to pure  $ZrO_2$  film ( $8.04 \times 10^{-3}$  GPa). Thus, the development of CeSZr based coating may lead to better surface protection of many components.

Key Words: Hardness, Ceria-Zirconia, Thin films, Nanostructure, EB-PVD

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